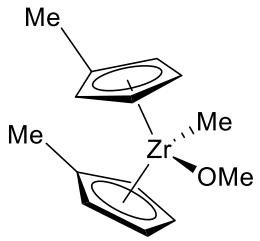
Catalog # B282591 Bis(methylcyclopentadienyl)(methyl)(methoxy)zirconium(IV), 98+%



Technical Notes:

1. Precursor for the atomic layer deposition of zirconium oxide using water or ozone as co-reactants.[1-6]

References:

1. *J. Electrochem. Soc..*, **2010**, *157 (10)*, G202-G210.
2. *Thin Solid Films,* **2010**, *519 (2)*, 666-673.
3. *Journal of Vacuum Science & Technology B: Microelectronics and Nanometer Structures Processing, Measurement, and Phenomena***, 2009,** *27*, 389.
4. *Chem. Mater.,* **2008***, 20 (17),* 5698-5705.
5. *Chemical vapor deposition,* **2008***, 14,* 358-365.
6. *Journal of Materials Chemistry,* **2008,** *28,* 3385-3390.